

40 Ni-V2

Nickel Ion Meter

Water quality inspection of Nickel Ion for plating Process

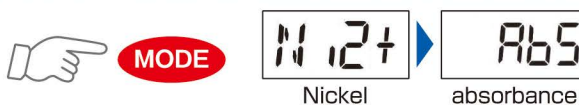


■ Nioxime Method Reagent



Model	Ni-V2
Measuring object	Nickel Ion
Measuring method	Nioxime Method
Measuring range	Nickel Ion :0.00~10.00mg/ℓ (Ni ²⁺) Absorbance:0.000~2.000Abs/cm
Repeatability	Within ±2%(FS)
Memory function	Max19 Data
Standard Component	Instrument, measuring Cell(4pcs) Reagent(Ni-V2-RA):50tests Carrying Case, Spoit

■ Nickel Ion & Abs can be measured with one single instrument



41 H₂O₂-V series Hydrogen peroxide density Meter

H₂O₂ measurement of plating liquid, etching liquid and disinfectant liquid



	High density	Medium density	Low density
Model	H ₂ O ₂ -V1	H ₂ O ₂ -V2	H ₂ O ₂ -V3
Measuring object	H ₂ O ₂ in copper plating liquid		H ₂ O ₂ in disinfectant liquid
Measuring range	0.0~120.0g/ℓ	0~1200mg/ℓ	0.00~25.00mg/ℓ
Measuring time	Approx. 1 minute		
reagent	1 kind (with 50 pieces)		

42 H₂SO₄-55

Sulfuric Acid Meter

Measurement of H₂SO₄ Density for Plating & Etching Process Liquid



Possible to measure Sulfuric Acid Density by 0-199g/ℓ

Model	H ₂ SO ₄ -55
Measuring Method	Light Absorbance Method
Measuring Range	0.0~199.9g/ℓ (H ₂ SO ₄)
Display	LCD 3·1/2 digits
Standard Components	Instrument (H ₂ SO ₄ -55), Measuring cell(4pcs) Reagent : H ₂ SO ₄ -RA 500mℓ (50 tests), Carrying Case. Micro-Pipette 100μℓ